

October 29, 2003

To: Commissioner of Patents and Trademarks  
Washington, D.C. 20231

Fr: George O. Saile     Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, N.Y. 12603

Subject:

**Divisional Patent Application of**  
Serial No.: 10/038,389 1/3/02

YING-LANG WANG, SHI-CHI LIN, YI-LUNG CHENG,  
CHI-WEN LIU, MING-HUA YOO, WEN-KUNG CHENG,  
JIAN-KWANG WANG

IMPROVED CMP PROCESS LEAVING NO RESIDUAL  
OXIDE LAYER OR SLURRY PARTICLES

**PRELIMINARY AMENDMENT**

Dear Sir:

This is a preliminary amendment for the above referenced Divisional Patent  
Application. Please amend the above identified application for patent as follows:

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States  
Postal Service as first class mail in an envelope addressed to: Commissioner of Patents  
and Trademarks, Washington, D.C. 20231, on Nov. 12, 2003

Stephen B. Ackerman, Reg. No. 37,761

Signature/Date

SB Ackerman 11/12/03